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REMARKS/DISCUSSION OF ISSUES

By this Amendment, Applicants amend claim 13 to correct a typographical error, and add claims 14-20.

Accordingly, claims 1-20 are pending in the application.

Applicants acknowledge the indication that claims 3, 7 and 8 define patentable subject matter and would be allowable if rewritten in independent form, including all limitations of their base claim and any intervening claims.

Applicants thank the Examiner for indicating that the drawings are acceptable, and for acknowledging the claim for priority and receipt of certified copies of all the priority documents.

New claims are added to at least partially restore the original range of claims that existed before multiple dependencies were removed in the preliminary amendment. No new matter is added.

Reexamination and reconsideration are respectfully requested in view of the following remarks.

35 U.S.C. § 102 & 103

The Office Action rejects: claims 1, 2, and 11-13 under 35 U.S.C. § 102 over Seiichi JP Pat. 60133758 ("Seiichi"); claims 4-6 under 35 U.S.C. § 102 over Seiichi in view of Yoshiharu; and claims 9-10 under 35 U.S.C. § 102 over Wong U.S. patent publication 2002/0187592 ("Wong").

Applicants respectfully traverse these rejections for at least the following reasons.

REQUEST FOR ENGLISH TRANSLATION OF CITED DOCUMENT

At the outset, the Office Action cites <u>Selichi</u> against claims 1, 2, 4-6 and 11-13. <u>Selichi</u> is published in Japanese, not English. MPEP 706.02 provides that:

"When an abstract is used to support a rejection, the evidence relied

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> upon is the facts contained in the abstract, not additional facts that may be contained in the underlying full text document. Citation of and reliance upon an abstract without citation of and reliance upon the underlying scientific document is generally inappropriate where both the abstract and the underlying document are prior art. See Ex parte Jones, 62 USPQ2d 1206, 1208 (Bd. Pat. App. & Inter. 2001) (unpublished). To determine whether both the abstract and the underlying document are prior art, a copy of the underlying document must be obtained and analyzed. If the document is in a language other than English and the examiner seeks to rely on that document, a translation must be obtained so that the record is clear as to the precise facts the examiner is relying upon in support of the rejection. The record must also be clear as to whether the examiner is relying upon the abstract or the full text document to support a rejection. ... In limited circumstances, it may be appropriate for the examiner to make a rejection in a non-final Office action based in whole or in part on the abstract only without relying on the full text document. In such circumstances, the full text document and a translation (if not in English) may be supplied in the next Office action."

Accordingly:

- 1. Rejections based on <u>Selichi</u> are inappropriate unless the Examiner has provided a full translation of that document, which he has not done here:
- 2. Rejections based on the English abstracts of <u>Selichi</u> are improper in any subsequent final Office action unless the Examiner has provided a translation of the full text document (not just the abstract), which the Examiner has not done here.

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Therefore, if the Examiner desires to maintain a rejection of any of Applicants' claims based on Sejichi in a Final Office action, Applicants respectfully request that he supply an English translation of the full text (not just the abstract) of the document, as required by MPEP 706.02.

Claim_1

Among other things, the method of claim 1 includes: (1) etching a layer structure in the third region; and (2) either removing the second patterned layer and etching the layer structure in the second region, or removing the first patterned layer and etching the layer structure in the first region.

Applicants respectfully submit that the cited Abstract of Seiichi does not disclose either of these features. Indeed, the Office Action wholly ignores and fails to make any mention whatsoever of the second feature mentioned above!

The Office Action maintains that the first, second, and third regions of Selichi are the source, gate and drain. Assuming that is correct, Applicants respectfully note that the Seilchi abstract does not disclose etching any layer structure in the drain (third) region, nor does it mention removing the second (gate) patterned layer and etching a layer structure in the second (gate) region, or removing the first (source) patterned layer and etching a layer structure in the first (source) region. Indeed, for what possible purpose would Seiichi print a patterned layer comprising a source, gate, or drain electrode, and then REMOVE the source, gate, or drain electrode!

Therefore, Seiichi's Abstract cannot possibly disclose the method of claim 1. Accordingly, Applicants respectfully submit that claim 1 is patentable over the

Claims 2 and 11-12

Claims 2 and 11-12 depend from claim 1 and are deemed patentable for at least the reasons set forth above with respect to claim 1.

Claim 13

cited art.

Among other things, the apparatus of claim 13 includes removing means, configured either to remove said first patterned layer and to leave at least part of said second patterned layer or to remove said second patterned layer and to leave at

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least part of said first patterned layer.

Applicants respectfully submit that the cited Abstract of <u>Seiichi</u> does not disclose such features. Indeed, the cited Abstract makes no mention whatsoever of removing any patterned layers formed by printing, nor would removal of <u>Seiichi</u>'s source, gate, or drain electrodes appear to make any sense.

Therefore, <u>Seiichi</u>'s Abstract cannot possibly disclose the method of claim 1.

Accordingly, Applicants respectfully submit that claim 1 is patentable over the cited art.

Claims 4-6

Claims 4-6 depend from claim 1. <u>Yoshiharu</u> does not remedy the shortcomings of <u>Seiichi</u>'s Abstract as set forth above with respect to claim 1. Therefore, claims 4-6 are deemed patentable over the prior art for at least the reasons set forth above with respect to claim 1, and for the following additional reasons.

Claim 5

Among other things, the method of claim 5 includes printing said first patterned layer having a first thickness and printing said second patterned layer having a second, different thickness.

Applicants respectfully submit that <u>Yoshiharu</u> does not disclose such a combination of features. In particular, the cited text at col. 4, lines 45-58 makes no mention of any two patterned layers, formed by printing, having different thicknesses from each other.

Accordingly, for at least these additional reasons, Applicants respectfully submit that claim 5 is patentable over the cited art.

Claim 6

Among other things, the method of claim 6 includes using a first ink for printing said first patterned layer and using a second ink for printing said second patterned layer.

Applicants respectfully submit that <u>Yoshiharu</u> does not disclose such a combination of features. In particular, the cited text at cols. 4 and 6 very clearly refer

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to two separate embodiments and do not disclose any method uses a first ink for printing said first patterned layer and a second ink for printing said second patterned layer.

Accordingly, for at least these additional reasons, Applicants respectfully submit that claim 6 is patentable over the cited art.

Claims 9-10

Claims 9-10 each depend from claim 1, and accordingly each include all of the features of claim 1, specifically including forming at least a first or second patterned layer by printing.

Applicant respectfully submits that <u>Wong</u> does not disclose forming at least a first or second patterned layer by printing. Furthermore, the Office Action does not even allege that <u>Wong</u> discloses forming at least a first or second patterned layer by printing. Indeed, the Office Action fails to even mention any of the specifically-recited features of claim 1 in its rejection of claims 9 and 10 over <u>Wong</u>.

Accordingly, for at least these reasons, Applicants respectfully submit that claims 9-10 are both patentable over the cited art.

NEW CLAIMS 14-20

New claims 14-20 all depend from claim 1 and are deemed patentable for at least the reasons set forth above with respect to claim 1.

CONCLUSION

In view of the foregoing explanations, Applicant(s) respectfully request(s) that the Examiner reconsider and reexamine the present application, allow claims 1-20 and pass the application to issue. In the event that there are any outstanding matters remaining in the present application, the Examiner is invited to contact Kenneth D. Springer (Reg. No. 39,843) at (571) 283.0720 to discuss these matters.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies to charge payment or credit any overpayment (except for the issue fee) to Deposit Account No. 50-0238 for any additional fees required under 37 C.F.R. §

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1.16 or under 37 C.F.R. § 1.17, particularly extension of time fees.

Respectfully submitted,

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Date: 31 July 2006

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